WHAT IS CLAIMED IS:

	2) 1	1. A matching network that can be coupled between an ac power
m) (b)	7 2	source and a load to reduce ac energy reflected from said load, said matching network
	3	comprising:
•	4	(a) a first transmission line that can be coupled to said ac power
	5	source; and
	6	(b) a second transmission line inductively coupled to said first
	7	transmission line, wherein said first and second transmission lines are inductively
	8	coupled for an inductive length, said inductive length being at least one wavelength of
312 is	9	ac energy supplied by said ac power source, wherein said second transmission line can
101; ea 121;	10	be coupled to said load to deliver ac energy from said first transmission line to said
. l _{en} i 	11	load.
nai:	1	2. The matching network of claim 1 wherein said inductive length
lji u	2	is at least 0.75 meters.
eal.	1	The matching network of claim 1 further comprising:
	2	(c) a trimming element coupled to said first transmission line and
	3	coupled to ground.
ral:		
	1	4. The matching network of claim wherein said first and second
	2	transmission lines within said inductive length are a constant fixed distance apart.
	1	5. The matching network of claim wherein said first and second
	2	transmission lines within said inductive length are positioned at a non-zero angle with
	3	respect to one another.
	3	respect to one another.
	1	6. The matching network of claim 5 wherein said first and second
	2	transmission lines each have a first and second end within said inductive length, and
	3	from said first end to said second end of said first and second transmission lines the
	4	distance between the transmission lines increases.
	1	7. The matching network of claim 1 wherein said first transmission
	2	line is comprised of a first plurality of coils, said second transmission is comprised of a
	3	second plurality of coils, and said first plurality of coils surround said second plurality
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J.B	W	9. A method for minimizing reflected ac power from a plasma
S	2	formed in a substrate processing chamber, said method comprising:
	3	coupling an ac power source generating ac energy of a specified
	4	wavelength to said plasma in said substrate processing chamber;
ļ.	5	coupling a matching network between said ac power source and said
	6	plasma, said matching network comprising a first transmission line and a second
	7	transmission line, wherein said first and second transmission lines are inductively
	8	coupled over an inductive length, said inductive length being at least one of said
	9	specified wavelength.
ia seli	1	10. The method of claim 9 wherein said first transmission line
(<u>[</u>]) 4,1	2	receives ac energy from said ac power source, said second transmission line inductively
1,71	3	receives ac energy from said first transmission line, and said second transmission line
	4	delivers ac energy to said plasma.
	1	11. The method of claim 9 wherein said first and second
	2	transmission lines within said inductive length are parallel.
	1	12. The method of claim 9 wherein, said first and second
	2	transmission lines within said inductive length have a non-zero angle with respect to
	3	one another.
	3	one another.
	1	12 The mathod of claim 0 wherein said first transmission line is

from said first end to said second end.

1

2

3

2

of coils.

14.

The matching network of claim 7 wherein said first plurality of

coil have a constant radius of curvature, said second plurality of coils have a first end

and a second end, and said second plurality of coils have a changing radius of curvature

comprised of a first plurality of coils, said second transmission is comprised of a

formed in a substrate processing chamber, said method comprising:

second plurality of coils, and said first plurality of coils surround said second plurality

A method for minimizing reflected ac power from a plasma

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Cr.	2 W.B	generating an ac power signal having a specified wavelength and
<i>J</i>	4	transmitting said signal to a first transmission line that is inductively coupled to a
A	5	second transmission line over an inductive length, wherein said inductive length is at
,	6	least one of said specified wavelength;
	7	transmitting said ac power signal from said second transmission line to a
	8	substrate processing chamber.
	1	15. The method of claim 14 wherein said ac power signal has a
	2	frequency range of operation between 100 KHz to 2.45 GHz and said inductive length
ļanii	3	is between 3000 and 0.12 meters.
 	1	16. The method of claim 14 wherein said ac power signal has a
1201 #11 12611	2	frequency between 350 KHz and 400 MHz and said inductive length is between 857
	3	meters and 0.75 meters.
(,F*)	1	17. An energy delivery system comprising:
is Įsali	2	an ac power source capable of generating an ac signal of at least
[3] [4]	3	100 KHz;
(]	4	a matching network having a first transmission line that can be coupled
 -= -	5	to said ac power source, a second transmission line inductively coupled to said first
	6	transmission line, wherein said first and second transmission lines are inductively
	7	coupled for an inductive length, saift inductive length being at least 0.75 meters; and
	8	a load coupled to said second transmission line.
	1	18. The matching network of claim 17 wherein said ac power source
	2	is an RF generator and said load is a plasma.
	1	19. A substrate processing system comprising:
	2	(a) an RF generator;
	3	(b) a substrate processing chamber; and
	4	(c) a matching network having a first and second transmission line, said
	5	first transmission line being coupled to said RF generator; said second transmission line
	6	being coupled to said substrate processing chamber, where said first and second

transmission lines are inductively coupled over an inductive length.